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PPLICATION NO.	FILI	NG DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
09.677,781	10.	02/2000	Katsuhide Manabe	PM273686	4206	
909	7590	02:12:2002				
PILLSBUR			EXAMINER			
1600 TYSON MCLEAN, V		VARD		MULPURI,	I, SAVITRI	
				ART UNIT	PAPER NUMBER	
				2812		
				DATE MAILED: 02/12/2002		

Please find below and/or attached an Office communication concerning this application or proceeding.



Application No. **09/677,781**

Applicant(s)

Manabe E T Al

Examiner

Savitri Mulpuri

Art Unit 2812



The MAILING DATE of this communication appe	ears on the cover sheet with the correspondence address		
Period for Reply			
A SHORTENED STATUTORY PERIOD FOR REPLY IS STATE MAILING DATE OF THIS COMMUNICATION.			
 Extensions of time may be available under the provisions of 3 after SIX (6) MONTHS from the mailing date of this comm 	37 CFR 1.136 (a). In no event, however, may a reply be timely filed		
- If the period for reply specified above is less than thirty (30) of be considered timely.	days, a reply within the statutory minimum of thirty (30) days will		
- If NO period for reply is specified above, the maximum statut	ory period will apply and will expire SIX (6) MONTHS from the mailing date of this		
	II, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). r the mailing date of this communication, even if timely filed, may reduce any		
Status			
1) X Responsive to communication(s) filed on Nov 2	8, 2001		
2a) ☐ This action is FINAL . 2b) 🔀 This	action is non-final.		
3) Since this application is in condition for allowan closed in accordance with the practice under Ex	ce except for formal matters, prosecution as to the merits is a parte Quayle, 1935 C.D. 11; 453 O.G. 213.		
Disposition of Claims			
4) X Claim(s) 53-118	is/are pending in the application.		
4a) Of the above, claim(s)	is/are withdrawn from consideration.		
5) Claim(s)	is/are allowed.		
6) X Claim(s) 53-118	is/are rejected.		
7) Claim(s)	is/are objected to.		
8) Claims	are subject to restriction and/or election requirement.		
Application Papers			
9) The specification is objected to by the Examine	г.		
10) The drawing(s) filed on is.	/are objected to by the Examiner.		
11) The proposed drawing correction filed on	is: a)□ approved b)□ disapproved.		
12) The oath or declaration is objected to by the Ex			
Priority under 35 U.S.C. § 119			
13) Acknowledgement is made of a claim for foreig	n priority under 35 U.S.C. § 119(a)-(d).		
a) \square All b) \square Some* c) \square None of:			
1. Certified copies of the priority documents	have been received.		
2. Certified copies of the priority documents	have been received in Application No		
application from the International B			
*See the attached detailed Office action for a list o			
14) Acknowledgement is made of a claim for dome	stic priority under 35 U.S.C. § 119(e).		
Attachment(s)			
15) Notice of References Cited (PTO-892)	18) Interview Summary (PTO-413) Paper No(s).		
16) Notice of Draftsperson's Patent Drawing Review (PTO-948)	19) Notice of Informal Patent Application (PTO-152)		
17) 💢 Information Disclosure Statement(s) (PTO-1449) Paper No(s)	20) Other:		

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DETAILED ACTION

This action is in response to the applicant's response filed on 11/28/01 cancelling 19-52.

Claim Rejections - 35 USC § 112

- 1. Claims 54, 56, 58,60, 62,64,66, ,68, 70,72,74,76,78,80,82,84,86,88,90,,92, 94, 96, 98,100, 102,104, 106,108,110,114,116,118 are rejected under 35 U.S.C. 112, first paragraph, as containing subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention. There is no support f or the range of claimed limitation silane to ammonia ratio of 6 X 10⁻¹⁰ to 2.6, X 10⁻⁸
- 2.Claims 111, 112 needs to be canceled because claim 111, 112 are depending on canceled claims 19, 20

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 53, 55,

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113,115,117 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kahn et al in combination with Koide et al and Keyyan Rahim Sayyah et al.

.Kahn et al discloses a method growing epitaxial layers by the following process steps: Providing a sapphire substrate; growing buffer layer of AlN; and then growing a gallium nitride compound layer on AlN buffer layer, wherein gallium nitride compound layer is AlGaN layer. Kahn et al discloses AlGaN layer with n-type dopant concentration approximately at 10 ¹⁸/cm ³. Kahn et al does not explicitly teach conductivity (1/resistivity). However, since Khan et al teaches the concentration of the n-type dopants is with the limit as of the claimed concentration, inherently the conductivity in the Khan et al must be with in the claimed range from 3.4 /ohm-cm to 130 /ohm cm. Khan et al does not examples n-type dopants. However, silicon is the most common and preferred element in the gallium nitride compound semiconductor materials.

Khan et al do not disclose following limitations (1) growing GaN by providing TMG at a temperature in the range of -15 to -12.5 C, (2) ratio of silane to TMG is 10^{-2} to 10^{-1} .

Koide et al disclsoes growing GaN by TMG a at a temperature in the range of -15 to -12.5 C (see left col. 1, lines 1-5). It would have been obvious to one of ordinary skill in the art to grow at low temeprature beacuse Koide process is to reduce parasitic reaction between metal organic compounds with ammonia therby producing AlGaN layers with controlled composition (see abstarct).

Keyyan Rahim Sayyah et al discloses the ratio of silane to TMG is 10^{-2} to 10^{-1} , which is within the range of claimed limitation of 0.1 to 3 in claims 53, 55. It would abve been obvius to

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one of ordinary skill in the art to the ratio of silane to TMG as sugguested by Keyyan Rahim Sayyah et al. Beacuse such range is suitable for growing GaN layers.

Exmainer position ove the claims 53-118 is now changed because of further reviw and analysis of the applied and cited patents and publications.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to S. Muklpuri whose telephone number is (703) 305-5184. The fax phone number for the organization where this application or proceeding is assigned is (703) 308-7722.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

SAVITRI MULPULI PRIMARY EXAMINER